

Advantages

- Increased tool throughput
- Decreased chemical costs
- Real time process monitoring
- Insurance against batch loss
- Improved cost of ownership

Applications

- Copper CMP
- Tungsten CMP
- Wet-Etch
- Cleans
- DSP+
- Nitride Etch
- PAN Etch
- Piranha Etch
- HF



Global Measurement Technologies' SemiChem Advanced Process Monitor offers process engineers the accuracy, reliability and flexibility for a higher degree of efficiency and consistency to meet the demands for higher yield and zero defect tolerance. In the ultra-competitive microelectronics industry, the most advanced facilities can ill afford highly expensive processes without the use of sophisticated monitoring and control to ensure consistent wafer manufacturing.

Quantitative chemical concentration is obtained with the SemiChem. Full on-line chemical monitoring allows real time correction of both composition and therefore stable control of the process conditions; product consistency is maintained.

Product yields are increased when a quantitative process composition is known. Variations that can affect product quality are immediately apparent and can be quickly correct before loss of product quality.

SemiChem APM

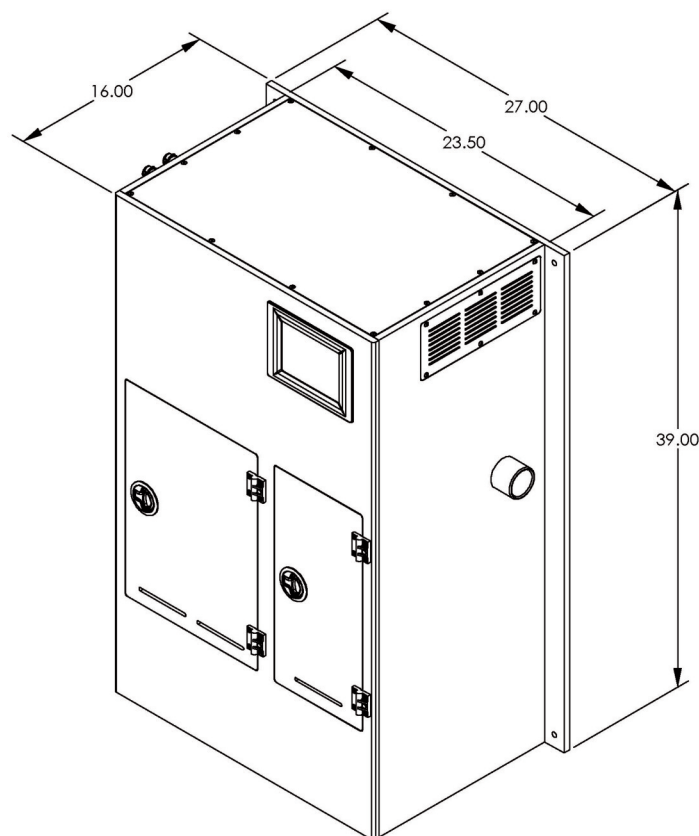
Specifications

Product Features

4 4...20mA Analog Outputs
8 Programmable relays
Ethernet & RS232 Serial
Color Touchscreen
Single Measuring Cell
Integrated Reagent Storage
Single Sample Point
1 5ml Digital Burette
Multiple Sensor Inputs

Product Options

Multiple Sample Points
Additional 5ml Digital Burettes
Additional Sensors
Safety Interlocks
Reagent Low Level Detection



Analysis Methods	Potentiometry/Standard Addition/Photometry
Accuracy ¹	+/- 0.2% of Displayed Value
Precision ¹	+/- 0.2% Relative Error
Measurement Time	Less than 5 minutes/analysis (application dependent)
Calibration Interval	at start-up ²
Sample Consumption	less than 5mls/analysis
Sample Size	0.05 to 5mls (application dependent)
Sample Temperature	up to 200°F (93°C)
Water Consumption	less than 1000mls/analysis
Sample Inlet/Return	less than 30psi 0.5 liter/minute 1/4" OD flare fitting 1" FPT containment coupling
Deionized Water	20-40psi 2.0 liters/minute 1/4" OD flare fitting
CDA	60-80psi 1/4" OD quick fitting
Process Drain	3/4" NPT gravity drain
Cabinet Drain	1/2" NPT gravity drain
Power	110/220 VAC, 50/60Hz, 1/0.5A field switchable
Exhaust	1 7/8" OD @ 17CFM
Overall Dimensions	39.00" H x 27.00" W x 16.00" D

1. Refers to "hardware" only. External factors such as application, chemistry, and process conditions can affect system accuracy and precision.
2. This does not include calibration of pH sensor. Please refer to the User's Guide for more information.
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Global Measurement Technologies, Inc.
7225 W. Oakland Street
Chandler, Arizona 85226
USA

Tel: +1-480-889-0263
Fax: +1-480-858-1801
Email: info@gmtechinc.com
Web: www.gmtechinc.com



SemiChem APM200 Wallmount Datasheet
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